

Refine Search

Search Results -

Terms	Documents
L12 same (hole or opening)	30

Database:

[US Pre-Grant Publication Full-Text Database](#)
[US Patents Full-Text Database](#)
[US OCR Full-Text Database](#)
[EPO Abstracts Database](#)
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Search:

Refine Search

Recall Text

Clear

Interrupt

Search History

DATE: Tuesday, May 03, 2005 [Printable Copy](#) [Create Case](#)

<u>Set</u> <u>Name</u> <u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
side by side		
DB=USPT; PLUR=YES; OP=OR		
<u>L13</u> L12 same (hole or opening)	30	<u>L13</u>
<u>L12</u> L11 same (titanium or "titanium nitride" or "titanium compound" or "titanium alloy")	122	<u>L12</u>
<u>L11</u> etch\$5 near10 (fluorine near5 gas)	2508	<u>L11</u>
<u>L10</u> etch\$5 near10 fluorine-containing-gas	0	<u>L10</u>
<u>L9</u> L6 same advantage\$	21	<u>L9</u>
<u>L8</u> L7 same advantage\$	0	<u>L8</u>
<u>L7</u> L6 same 50:1	0	<u>L7</u>
<u>L6</u> L5 same semiconductor	292	<u>L6</u>
<u>L5</u> etch\$5 near10 "high aspect ratio"	1325	<u>L5</u>
<u>L4</u> etch\$5 and "high aspect ratio"	6139	<u>L4</u>
<u>L3</u> 6693038	1	<u>L3</u>
<u>L2</u> L1 and NF3	0	<u>L2</u>

L1 6720256

4 L1

END OF SEARCH HISTORY

Refine Search

Search Results -

Terms	Documents
L20 and plasma and (fluorine near5 gas)	7

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Search:

L21		<input style="border: none; background-color: inherit; color: inherit; font-size: inherit; padding: 0; margin: 0;" type="button" value="Refine Search"/>
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Search History

DATE: Tuesday, May 03, 2005 [Printable Copy](#) [Create Case](#)
Set Name Query
 side by side

Hit Count Set Name
 result set

DB=USPT; PLUR=YES; OP=OR

<u>L21</u>	L20 and plasma and (fluorine near5 gas)	7	<u>L21</u>
<u>L20</u>	L19 and (etch\$5 near7 lateral\$5)	13	<u>L20</u>
<u>L19</u>	L18 and (etch\$5 near5 opening near5 gas)	75	<u>L19</u>
<u>L18</u>	opening near5 expos\$4 near7 surface	9452	<u>L18</u>
<u>L17</u>		1	<u>L17</u>
<u>L16</u>	5875205 and gasket	0	<u>L16</u>
<u>L15</u>	L6 and gasket	0	<u>L15</u>
<u>L14</u>	L7 and gasket	0	<u>L14</u>
<u>L13</u>	L12 and gasket	5	<u>L13</u>
<u>L12</u>	6265246	8	<u>L12</u>
<u>L11</u>	6228675	11	<u>L11</u>
<u>L10</u>	L5 and gasket and (wafer or substrate)	5	<u>L10</u>
<u>L9</u>	l6 and (gasket and (wafer or substrate))	0	<u>L9</u>
<u>L8</u>	L7 and gasket and (wafer or substrate)	0	<u>L8</u>

<u>L7</u>	6556608	1	<u>L7</u>
<u>L6</u>	5981945	10	<u>L6</u>
<u>L5</u>	6265246	8	<u>L5</u>
<u>L4</u>	6228675	11	<u>L4</u>
<u>L3</u>	6376280	4	<u>L3</u>
<u>L2</u>	6429511	6	<u>L2</u>
<u>L1</u>	6787897	1	<u>L1</u>

END OF SEARCH HISTORY